

IN THE ABSTRACT OF THE DISCLOSURE:

Please delete the present Abstract of the Disclosure and replace it with the following new Abstract of the Disclosure:

A lithographic projection apparatus includes a radiation system for providing a projection beam of radiation, a support structure for supporting a patterning device, the patterning device serving to pattern the projection beam according to a desired pattern, a substrate table for holding a substrate, a projection system for projecting the patterned beam onto a target portion of the substrate, an illumination system for conditioning the beam of radiation beam so as to provide a conditioned radiation beam so as to be able to illuminate said patterning means, and a beam delivery system including redirecting elements for redirecting and delivering the projection beam from the radiation system to the illumination system. The radiation beam is arranged to have a predetermined polarization state and the redirecting elements are arranged to provide a minimum radiation loss in relation to the predetermined polarization state of the radiation beam.